

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L10	1	7 and (third with order with polynomial)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:27
L9	1	7 and (third-order with polynomial)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:27
L8	1	7 and (two-dimensional or (two adj dimensional) or dimensional)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:26
L3	2	(lithography with tool) and (tool with correct\$3) and (select\$3 with position with field with exposure) and (calculat\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:23
L7	2	5 and polynomial	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:20
L6	1	5 and (polynomial with equation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:20
L2	1	(lithography with tool) and (tool with correct\$3) and (select\$3 with position with field with exposure) and (calculat\$3 with correct\$3) and (polynomial with equation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:20
L5	2	3 and (set with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:18
L4	1	3 and ((record\$3 or monitor\$3 or receiv\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:18

L1	0	(lithography with tool) and (tool with correct\$3) and (select\$3 with position with field with exposure) and (calculat\$3 with correct\$3) and (ppolynomial with equation)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:14
S12 4	1	(lithography with tool) and ((test\$3 with array) same (pattern with cell)) and (tool with correct\$3) and (select\$3 with position with field exposure) and (calculat\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 13:13
S11 9	161	(lithography with tool) and (tool with correct\$3) and (select\$3 with position with field exposure)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/05 12:48
S12 3	2	"6654703".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 19:24
S11 8	4	S117 and elongat\$3 and space	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 19:24
S12 2	2	"6737207".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:52
S70	12	S68 and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:52
S12 1	2	S119 and (monitor\$3 with test with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:47
S12 0	0	S119 and (record\$3 with test with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:47
S11 5	6	(lithography with tool) and (elongat\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:44

S117	20	S116 and (box-in-box near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:11
S116	51	(lithography with tool) and box-in-box	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 18:10
S4	0	(electron with beam with lithography with tool) and (three with elongat\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 17:22
S114	9	(image with quality with evaluat\$3) and (test\$3 array) and (astigmatism with correction) and (focus with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 12:02
S113	14	(image with quality with evaluat\$3) and (test\$3 array) and (astigmatism with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/20 12:01
S77	0	(image with quality with evaluat\$3) and (test\$3 array) and (width with space\$1) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:08
S112	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and (astigmatism with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:07
S94	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and lithography and correct\$3 and (test\$3 with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 22:07
S111	0	S106 and (accuracy with quality) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:54
S110	0	S106 and (high\$3 with image) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:53

S109	0	S106 and (high\$3 with quality) and (record\$3 or monitor\$3 or stor\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:53
S108	0	S106 and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S107	0	S106 and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S105	6	(image with quality with evaluat\$3) and field and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:52
S106	3	("5409538" "5790254" "5968691").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2004/12/19 21:50
S104	0	(image with quality with evaluat\$3) and array and field and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:48
S103	0	(image with quality with evaluat\$3) and array and (sub-field or subfield) and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:48
S102	0	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield) and (high\$3 with quality) and ((record\$3 or monitor\$3 or stor\$3) with test\$3 with correct\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:47
S24	14	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 21:46
S101	11	(evaluat\$3 with image) and (field with position) and (test\$3 with array) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 19:00

S10 0	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 19:00
S99	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography and substrate	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:59
S98	0	((evaluat\$3 with image) same (field with position)) and (test\$3 with array) and lithography and substrate and correct\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:58
S97	0	((evaluat\$3 near2 image) same (field with position)) and (test\$3 with array) and lithography and substrate and correct\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:57
S96	1	(evaluat\$3 near2 image) and (test\$3 with array) and lithography and correct\$3 and (test\$3 with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:55
S95	0	(evaluat\$3 near2 image near2 quality) and (test\$3 with array) and lithography and correct\$3 and (test\$3 with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:52
S93	0	((evaluat\$3 near2 image near2 quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:52
S92	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:51
S91	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and correct\$3 and (test with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:51
S90	0	((evaluat\$3 adj image adj quality) same (test\$3 with array)) and lithography and (test\$3 with correct\$3) and (test with position) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:50

S89	2	(test\$3 with array) and lithography and (test\$3 with correct\$3) and image and (test with position) and (test with cell) and (image with quality)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:48
S88	4	(test\$3 with array) and lithography and (test\$3 with correct\$3) and image and (test with position) and (test with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:44
S87	2	(test\$3 with array) and (lithography with test\$3) and image and (test with position) and (test with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:39
S1	0	10/604051	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/19 18:15
S86	0	(image with evaluat\$3) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:43
S85	0	(image with quality) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:43
S84	1	(image with quality) and (test\$3 array) and ((sub-field or subfield) with test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:42
S79	0	(image with quality with evaluat\$3) and (test\$3 array) and ((sub-field or subfield) with test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:42
S83	0	(image with quality with evaluat\$3) and (test\$3 with array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:36
S82	1	(image with quality with evaluat\$3) and (test\$3 array) and (pattern near2 cell) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:35

S81	0	(image with quality with evaluat\$3) and (test\$3 array) and (pattern near2 cell) and (sub-field or subfield) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:32
S80	3	(image with quality with evaluat\$3) and (test\$3 array) and ((sub-field or subfield) with test\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:32
S78	15	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:29
S76	60	(image with quality with evaluat\$3) and (test\$3 array) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:28
S75	0	(image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:21
S74	2	(test with pattern with cell) and (test near2 array) and (wafer or mask or semiconductor or chip) and (width with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:17
S68	324	(test with pattern with cell) and (test near2 array) and (wafer or mask or semiconductor or chip)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:16
S73	10	(pattern adj cell) and (elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:09
S72	0	(pattern adj cell) and (range with elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:09
S71	0	(lithography with tool) and (range with elongated with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:08

S44	0	(lithography with tool) and ((tool with correction) same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 15:07
S69	0	S68 and (image with quality with evaluat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:08
S66	162	(test with pattern with cell) and (test near2 array) and (wafer or mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:06
S67	22	S66 and (test\$3 with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:02
S60	362	(test with pattern with cell) and (test near2 array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 14:01
S65	6	S60 and (test with position) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:58
S64	6	S60 and (test with position) and substrate and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:58
S61	0	S60 and (sub-field or subfield) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:56
S63	1	S60 and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:53
S6	1	(electron with beam with lithography with tool) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:53

S62	1	S60 and (sub-field or subfield)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:52
S27	0	((image with quality with evaluat\$3) and (test\$3 near2 array) and (sub-field or subfield)) and lithography and (test\$3 near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:52
S59	2	(test with pattern with cell) and (blank near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:50
S58	26	(test with pattern with cell) and (blank with pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:43
S57	0	(test with pattern with cell) and shape-in-shape and box-in-box and (blank with pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:34
S25	4	((image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 13:27
S40	3	lithography and (evaluat\$3 with quality with image) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/12/18 12:59
S53	22	"702"/\$.ccls. and (image with quality) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:36
S52	1	("702"/\$.ccls. and (image with quality) and lithography) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:35
S51	0	("702"/\$.ccls. and (image with quality with evaluat\$3)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:34

S50	22	"702"/\$.ccls. and (image with quality with evaluat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:34
S49	5	(lithography and (correction same (select\$3 with field with position))) and (image with quality)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 13:31
S48	0	(lithography and (correction same (select\$3 with field with position))) and (test\$3 with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55
S47	0	(lithography and (correction same (select\$3 with field with position))) and (record\$3 with test\$3 with correction)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55
S46	16	lithography and (correction same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:55
S45	0	(lithography with tool) and (correction same (select\$3 with field with position))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:54
S43	0	(lithography with tool) and (tool with correction with select\$3 with field with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/08 12:53
S42	5	lithography and (evaluat\$3 with quality with image) and (correct\$3 with field with position)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 13:09
S41	2	lithography and (evaluat\$3 with quality with image) and polynomial	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:41
S39	6	(electron with beam with lithography) and (evaluat\$3 with quality with image)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:32

S38	2	((electron with beam with lithography) and (evaluat\$3 with quality with image)) and (array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:29
S37	0	((electron with beam with lithography) and (evaluat\$3 with quality with image)) and (test\$3 with array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:29
S31	0	(electron with beam with lithography) and (equivalent with width) and box and field and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:28
S36	5	((electron with beam with lithography) and (equivalent with width) and (length\$3 with space)) and pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:22
S35	0	((electron with beam with lithography) and (equivalent with width) and (length\$3 with space)) and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:21
S34	5	(electron with beam with lithography) and (equivalent with width) and (length\$3 with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:21
S33	0	(electron with beam with lithography) and (equivalent with width) and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:19
S32	0	(electron with beam with lithography) and (equivalent with width) and field and (lengthen with space)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:19
S10	10	(electron with beam with lithography) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:18
S30	1	(electron with beam with lithography) and (equivalent with width) and test\$3 and (pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:02

S29	0	(electron with beam with lithography) and (equivalent with width) and (test\$3 with pattern with cell)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:02
S8	0	((electron with beam with lithography with tool) and (equivalent with width)) and elongat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/07 12:00
S28	0	((image with quality with evaluat\$3) and (test\$3 near2 array) and (sub-field or subfield)) and lithography	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 21:03
S26	0	((image with quality with evaluat\$3) and (test\$3 array) and (sub-field or subfield)) and lithography and (test\$3 near2 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 21:02
S22	23	electron with beam with lithography with tool with image	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:39
S23	2	"6654703".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:33
S2	0	electron with beam with lithography with tool with test with pattern with cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:31
S21	0	((pattern with test\$3 with cell) and (elongat\$3 with space\$1)) and (lithography with tool)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29
S20	13	(pattern with test\$3 with cell) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29
S19	0	(pattern with test\$3 with cell) and (elongat\$3 with space\$1) and (width with range) and border	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:29

S18	0	(pattern with test\$3 with cell) and (elongat\$3 with space\$1) and (width with range) and box and field and spot and border	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:28
S17	5	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:26
S15	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:13
S16	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)) and (equivalent with width)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12
S14	16	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (width with range)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12
S13	0	((electron with beam with lithography) and (elongat\$3 with space\$1)) and (elongat\$3 with space\$1) same (width with range))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:12
S12	67	(electron with beam with lithography) and (elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:11
S11	4	((electron with beam with lithography) and (equivalent with width) and box and field) and pattern and cell	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:09
S9	0	(electron with beam with lithography with tool) and (equivalent with width) and box and field	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:08
S7	3	(electron with beam with lithography with tool) and (equivalent with width)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 20:08

S5	0	(electron with beam with lithography with tool) and (three with elongat\$3 with space\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 19:48
S3	284	electron with beam with lithography with tool	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/11/06 19:40